

**Amendments to the Claims:**

1. (Previously presented) A front-end array process for making a liquid crystal display panel, comprising:  
5        depositing a molybdenum-containing metal layer on a glass substrate;  
         forming a patterned photoresist on said molybdenum-containing metal layer,  
             wherein said patterned photoresist defines a gate and word line array pattern;  
             and  
             using said patterned photoresist as an etching mask, uniformly etching said  
10        molybdenum-containing metal layer to form said gate and word line array  
             pattern having substantially oblique sidewalls, wherein said etching of said  
             molybdenum-containing metal layer uses gas mixture.
2. (Original) The front-end array process for making a liquid crystal display panel  
15        according to claim 1 wherein after said etching of said molybdenum-containing metal  
             layer, an over etching is carried out.
3. (Previously presented) The front-end array process for making a liquid crystal  
display panel according to claim 1 wherein fluorine/oxygen containing gas mixture is  
20        SF<sub>6</sub>/O<sub>2</sub> having a ratio of about 700sccm/300sccm.
4. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 1 wherein said etching of said molybdenum-containing metal layer  
is executed under a process pressure higher than 25 mTorr.  
25
5. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 1 wherein said etching of said molybdenum-containing metal layer  
is further controlled by a source power, a bias power, process pressure, oxygen  
flowrate and flowrate of fluorine containing gas.  
30
6. (Original) The front-end array process for making a liquid crystal display panel

according to claim 1 wherein said molybdenum-containing metal layer is a dual-metal layer.

7. (Previously presented) The front-end array process for making a liquid crystal display panel according to claim 6 wherein said dual-metal layer is Mo/AlNd, MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and Al are bottom layers.

8. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is detected by an end-point detection method at an wavelength of about 704nm.

9. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/fluorine containing.

10. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine containing.

11. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine/fluorine containing.

12. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is SiF<sub>6</sub>/O<sub>2</sub> containing.

13. (Currently amended) A front-end array process for making a liquid crystal display panel, comprising:  
depositing a molybdenum-containing metal layer on a glass substrate;  
forming a patterned photoresist and defining a gate and word line array pattern on said molybdenum-containing metal layer; and  
etching said molybdenum-containing metal layer by using fluorine/oxygen containing gas mixture containing SF<sub>6</sub>/O<sub>2</sub> with a ratio of about

700sccm/300sccm, and using said patterned photoresist as an etching mask  
to form said gate and word line array pattern.

14. (Previously presented) The front-end array process for making a liquid crystal  
5 display panel according to claim 13 wherein said gate and word line array pattern  
have substantially oblique sidewalls.
15. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein after said etching of said molybdenum-containing  
10 metal layer, an over etching is carried out.
16. (Canceled)
17. (Original) The front-end array process for making a liquid crystal display panel  
15 according to claim 13 wherein said etching of said molybdenum-containing metal  
layer is executed under a process pressure higher than 25 mTorr.
18. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein said etching of said molybdenum-containing metal  
20 layer is detected by an end-point detection method at an wavelength of about  
704nm.
19. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein said molybdenum-containing metal layer is a  
25 dual-metal layer.
20. (Previously presented) The front-end array process for making a liquid crystal  
display panel according to claim 19 wherein said dual-metal layer is Mo/AlNd,  
MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and  
30 Al are bottom layers.